

PATENT NUMBER

2

<p><i>M.H.</i> <b>D.I.P.E.</b></p> <p><b>SCANNED</b> <i>En</i> <b>AC 3</b> <i>LA</i></p> <p><b>Q.A.</b></p>	<p><b>PATENT DATE</b></p>
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APPLICATION NO. 09/729339	CONT/PRIOR 1 F	CLASS 438	SUBCLASS 29	ART UNIT <del>2018</del> 18	EXAMINER Q. HOANG
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APPLICANTS  
Kyoichi Suwa

TITLE  
Mask, exposure method, line width measuring method, and method for manufacturing semiconductor devices

PTO-2040  
12/89

ISSUING CLASSIFICATION														
ORIGINAL					CROSS REFERENCE(S)									
CLASS		SUBCLASS			CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)								
INTERNATIONAL CLASSIFICATION.														

<input type="checkbox"/> <b>TERMINAL DISCLAIMER</b>	<b>DRAWINGS</b>			<b>CLAIMS ALLOWED</b>	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner) (Date)			<b>NOTICE OF ALLOWANCE MAILED</b>	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____ _____ _____	_____ (Primary Examiner) (Date)			<b>ISSUE FEE</b>	
				Amount Due	Date Paid
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	_____ (Legal Instruments Examiner) (Date)			<b>ISSUE BATCH NUMBER</b>	
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